

Abstract

The invention concerns a microstructure comprising an adhesive layer between a substrate and a photo-patternable layer, arranged on at least one face of the substrate. The adhesive layer is photosensitive and consists of a negative resin comprising at least one polymer of the family of elastomers and at least one photo-initiating component, in solution in an aromatic solvent. The photo-patternable layer consists of at least one negative epoxy resin. The method of fabrication of such a microstructure comprises spreading and drying the adhesive layer prior to depositing the photo-patternable layer. The adhesive layer can be exposed through a mask and developed, prior to the deposition of the photo-patternable layer.